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Direct Phenol Synthesis by Selective Oxidation of Benzene with Molecular Oxygen on a N-interstitial Re Cluster/Zeolite Catalyst**

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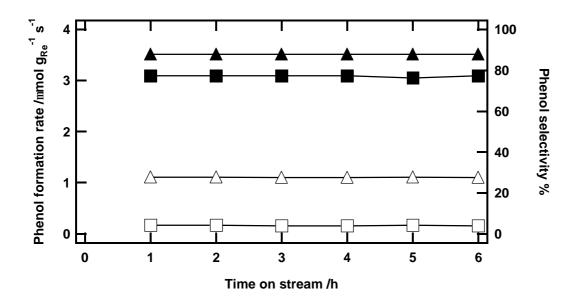
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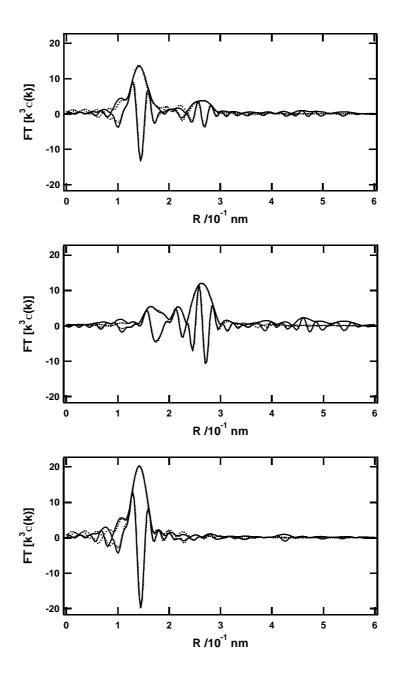
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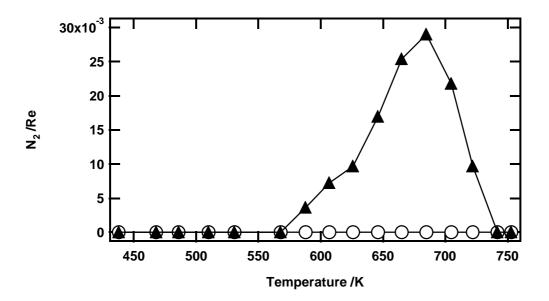
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Supporting Information 1. Catalytic performances for the selective benzene oxidation under the steady-state conditions on the Re/HZSM-5 catalyst (Re: 0.58 wt%, $SiO_2/Al_2O_3 = 19$) at 553 K. \bot : phenol formation rate on Re-CVD/HZSM-5, .: phenol selectivity on Re-CVD/HZSM-5, .: phenol formation rate on Re-impreg/HZSM-5, .: phenol selectivity on Re-impreg/HZSM-5.



Supporting Information 2. Re L-edge EXAFS Fourier-transforms for Re/HZSM-5 (Re: 0.58 wt%, CVD, $\text{SiO}_2/\text{Al}_2\text{O}_3 = 19$) after He treatment (top), after the NH $_3$ treatment for 2 h (middle), and after the steady-state reaction (bottom). Solid and dotted spectra represent observed and fitted data (absolute and imaginary parts), respectively.



Supporting Information 3. N_2 TPD spectra for the Re/HZSM-5 catalyst (Re: 0.58 wt%, CVD, $SiO_2/Al_2O_3 = 19$) (.) and HZSM-5 (.), treated with NH₃ at 553 K for 2 h.